

- 1 1. A method comprising:
2 forming a photoresist from a branched chain
3 scission polymer.
- 1 2. The method of claim 1 including providing
2 scissionable linkages and nonscissionable linkages in said
3 polymer.
- 1 3. The method of claim 1 including providing a
2 scionable linkage in a branch of said polymer.
- 1 4. The method of claim 1 including forming a
2 photoresist including a polymer having a molecular weight
3 greater than 10,000 Daltons.
- 1 5. The method of claim 1 including forming a
2 photoresist including a polymer having a branch having a
3 molecular weight greater than 5000 Daltons.
- 1 6. The method of claim 1 including forming a polymer
2 including oligo-4-hydroxystyrene.
- 1 7. The method of claim 6 including forming tertiary
2 carbonated linked branches.

1 8. The method of claim 6 including forming an oligo-
2 1,4-dihydroxyphenylcarbonate-bis tertiary alcohol.

1 9. The method of claim 8 including appending a
2 tertiary alcohol carbonate side chain on said polymer.